Approved by Examiner 4/5/04 TW

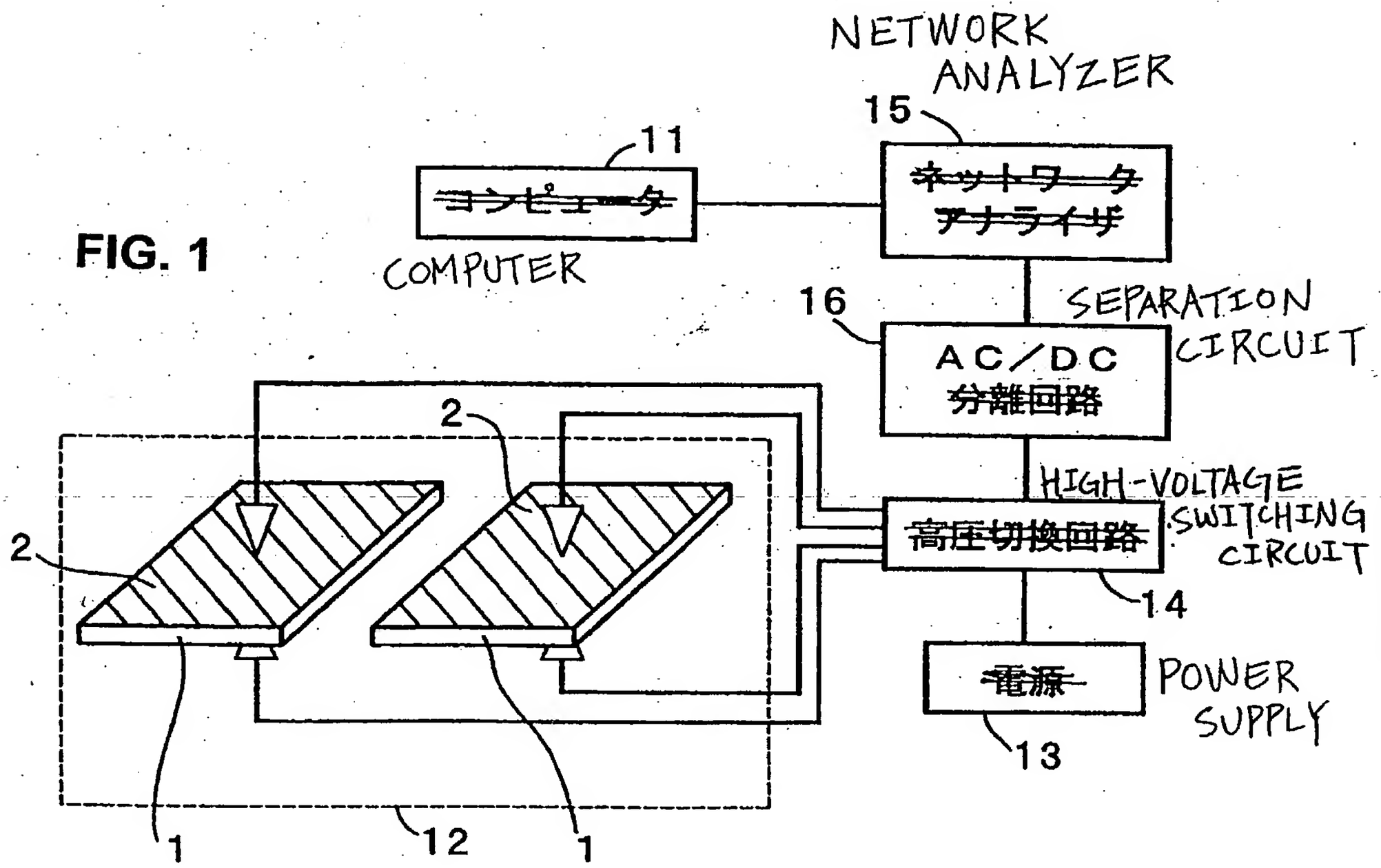

FIG. 1

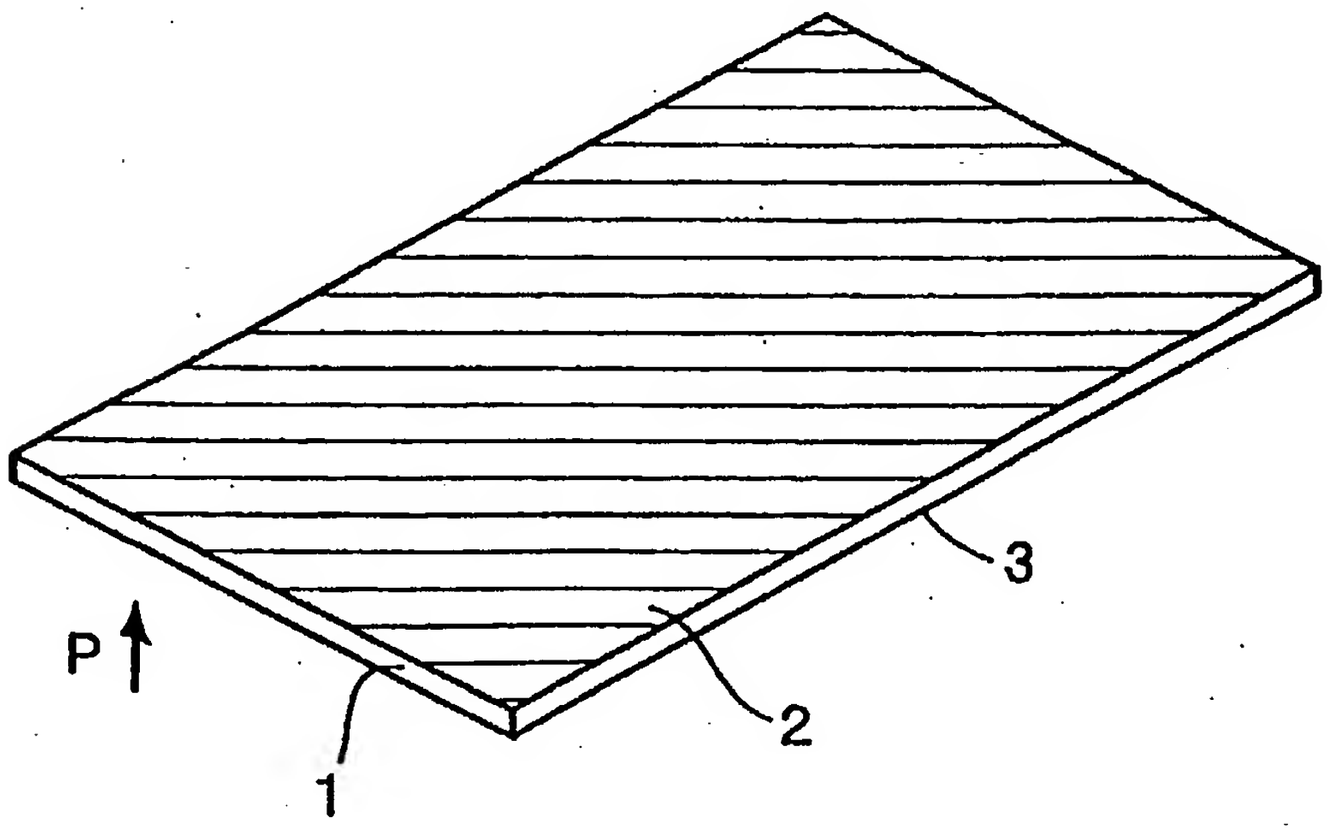

FIG. 2

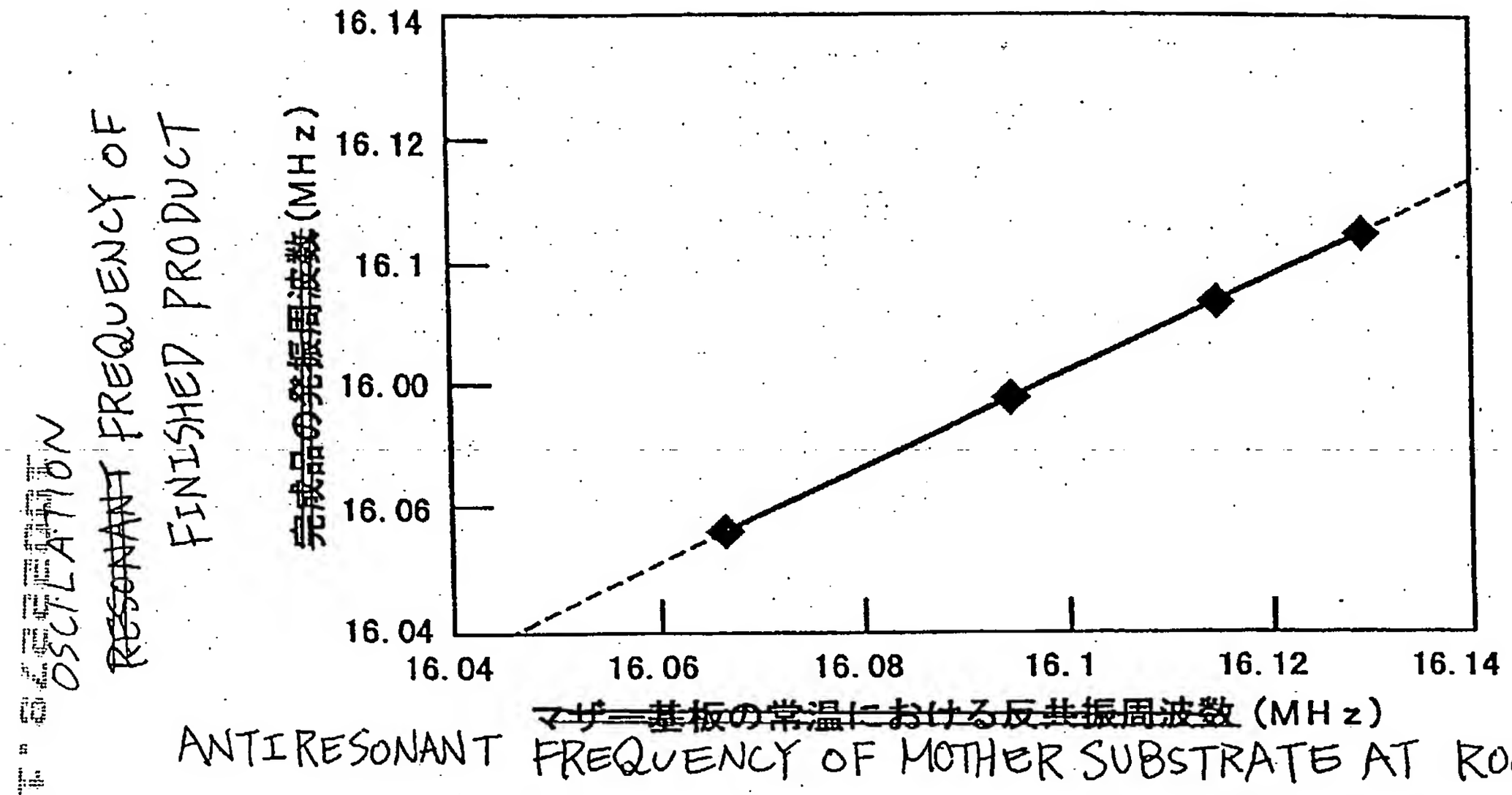
16.14
16.12
16.1
16.00
16.06
16.04
16.04
16.06
16.08
16.1
16.12
16.14
完成品の発振周波数 (MHz)
マザー基板の常温における反共振周波数 (MHz)
ANTIRESONANT FREQUENCY OF MOTHER SUBSTRATE AT ROOM TEMPERATURE
RESONANT FREQUENCY OF FINISHED OSCILLATION

FIG. 5

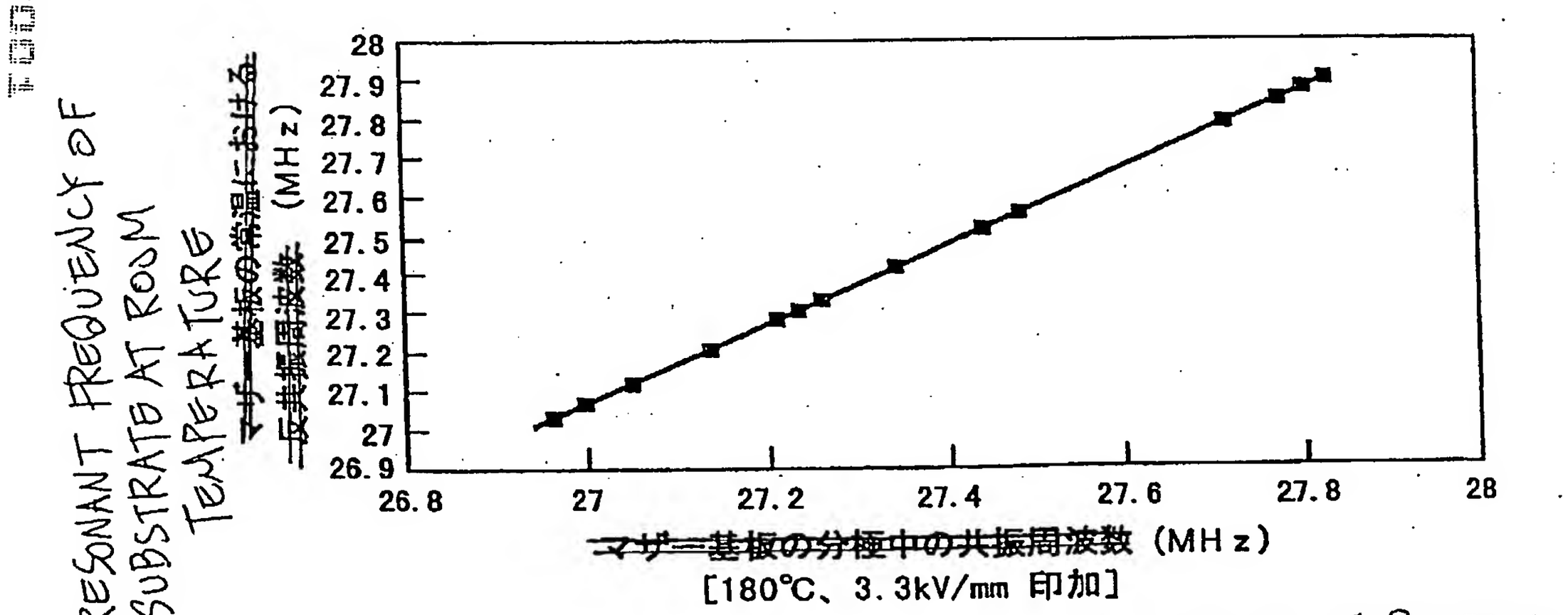
28
27.9
27.8
27.7
27.6
27.5
27.4
27.3
27.2
27.1
27
26.9
26.8
27
27.2
27.4
27.6
27.8
28
マザー基板の分極中の共振周波数 (MHz)
[180℃、3.3kV/mm 印加]
ANTIRESONANT FREQUENCY OF MOTHER SUBSTRATE AT ROOM TEMPERATURE
RESONANT FREQUENCY OF MOTHER SUBSTRATE DURING POLARIZATION

FIG. 6

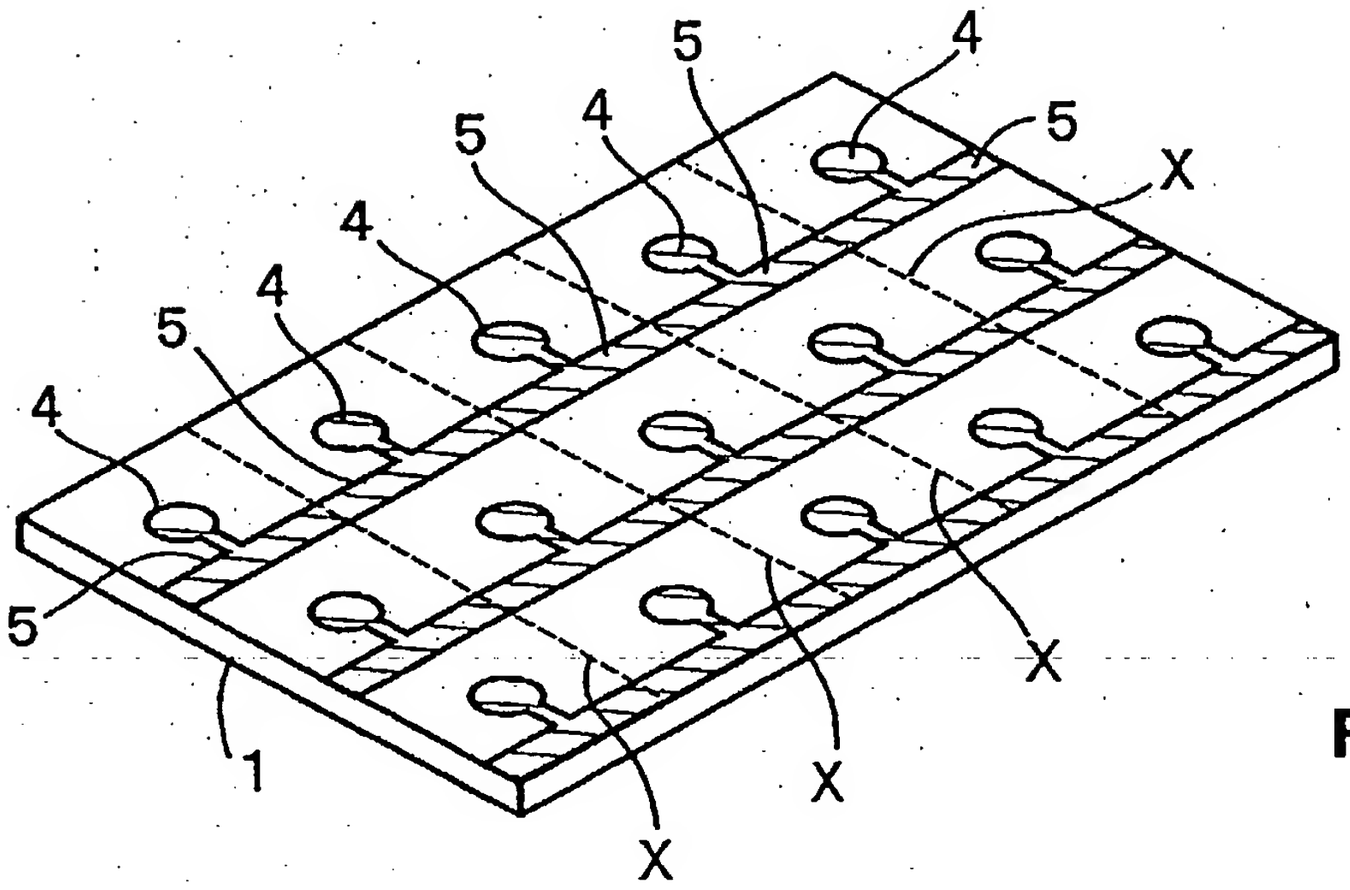

FIG. 3

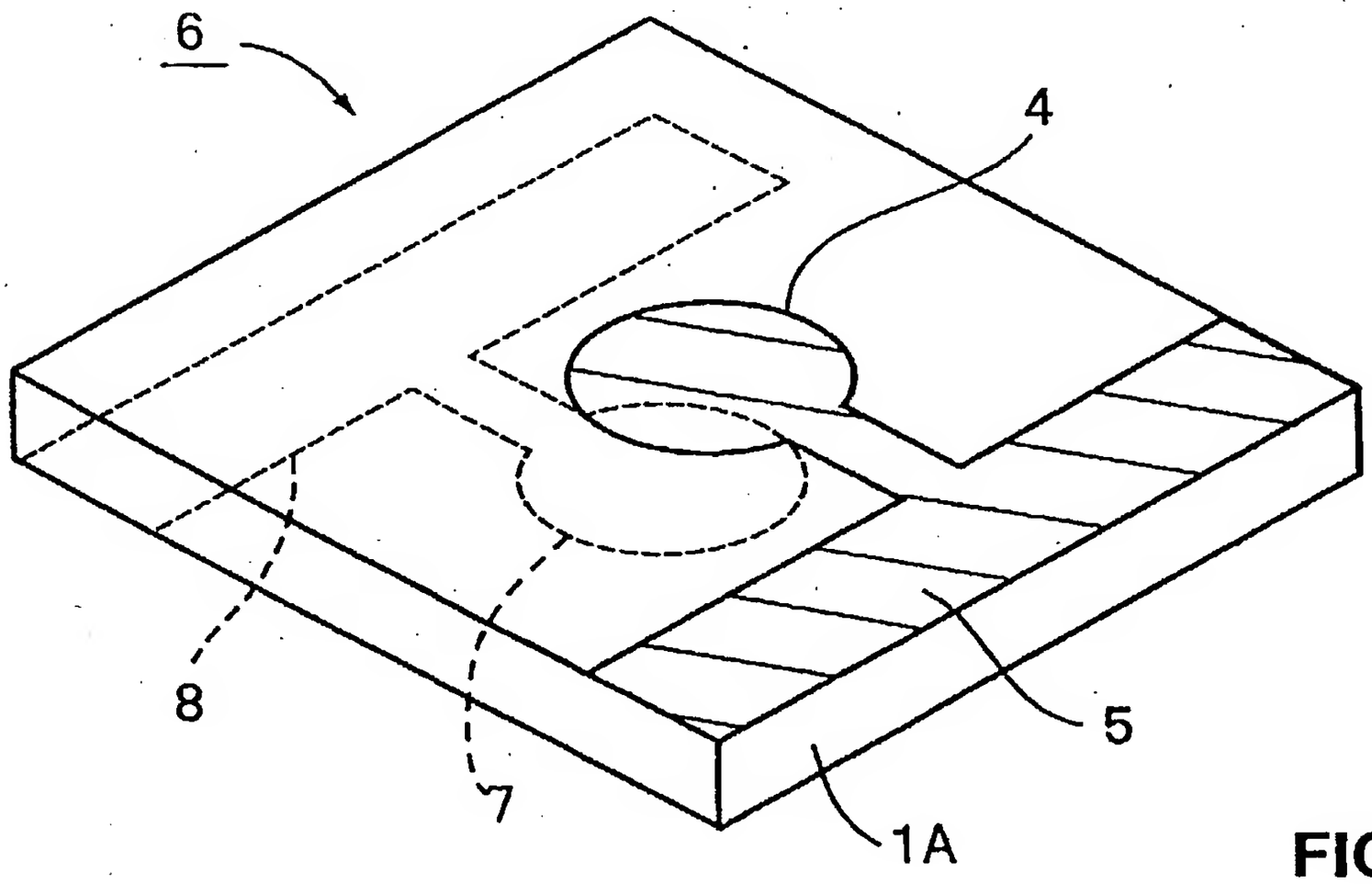

FIG. 4

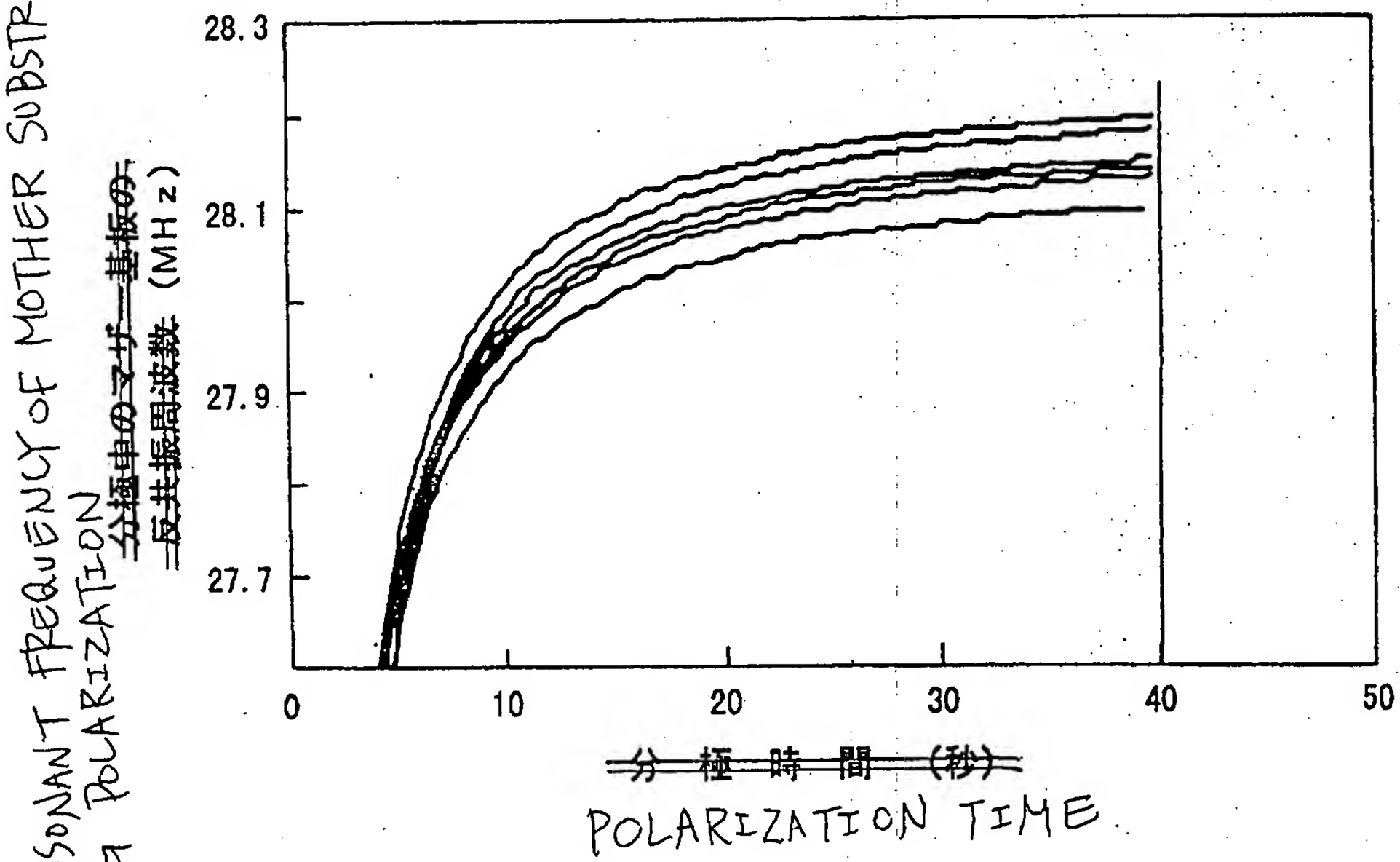
ANTIRESONANT FREQUENCY OF MOTHER SUBSTRATE
DURING POLARIZATION
分極中の子ー基板の
反共振周波数（MHz）
28.3
28.1
27.9
27.7
0
10
20
30
40
50
分極時間（秒）
POLARIZATION TIME

FIG. 7

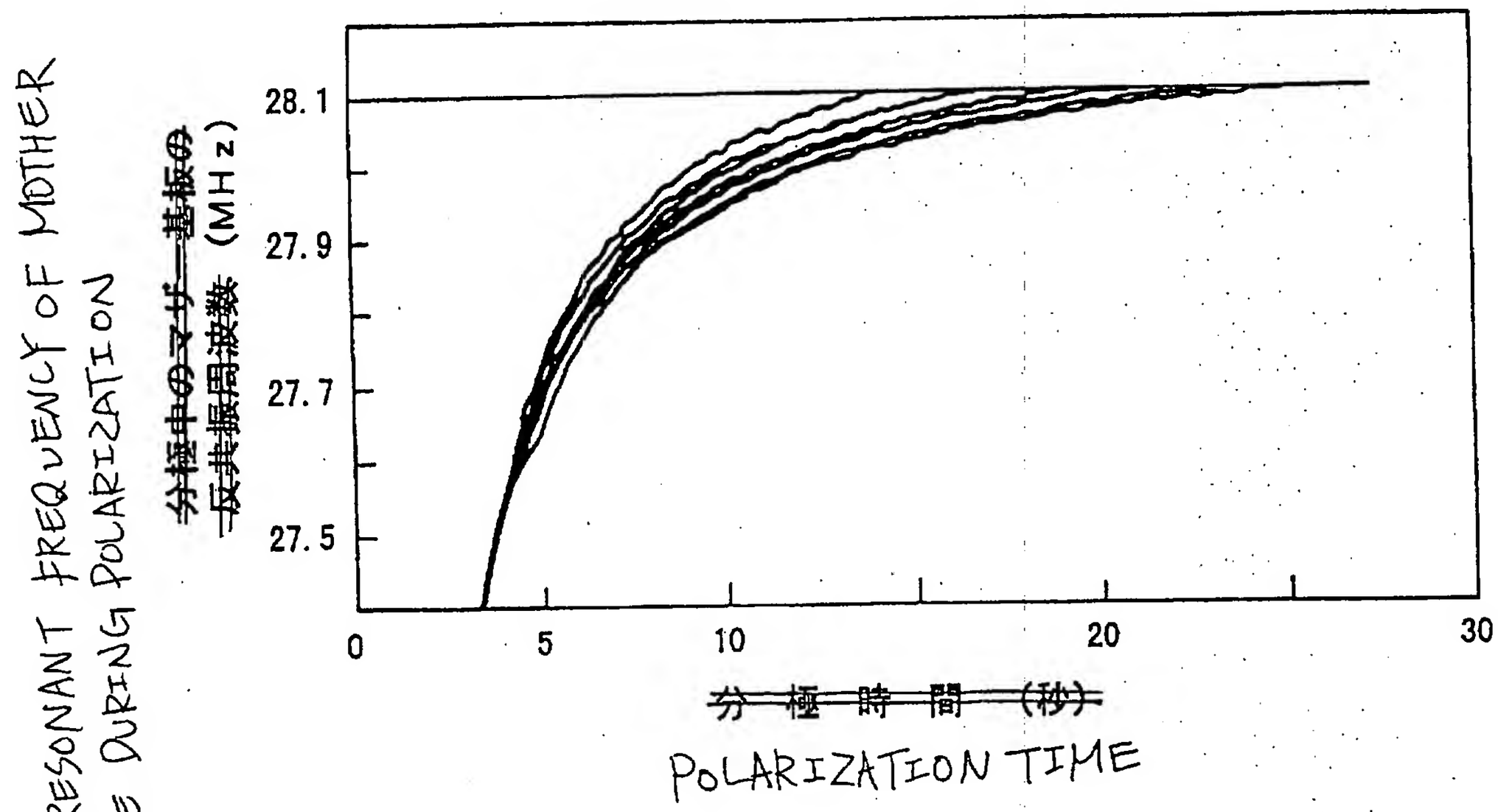
28.1
27.9
27.7
27.5
0
5
10
20
30
分極時間（秒）
POLARIZATION TIME
分極中のマザー基板の
反共振周波数（MHz）
ANTIRESONANT FREQUENCY OF MOTHER
SUBSTRATE DURING POLARIZATION

FIG. 8

APPLN. FILING DATE: DECEMBER 20, 2001
TITLE: MANUFACTURING METHOD FOR CERAMIC OSCILLA[redacted]
INVENTO[redacted]: NAOKI FUJII ET AL.
APPLICATION SERIAL NO: 10/022,278

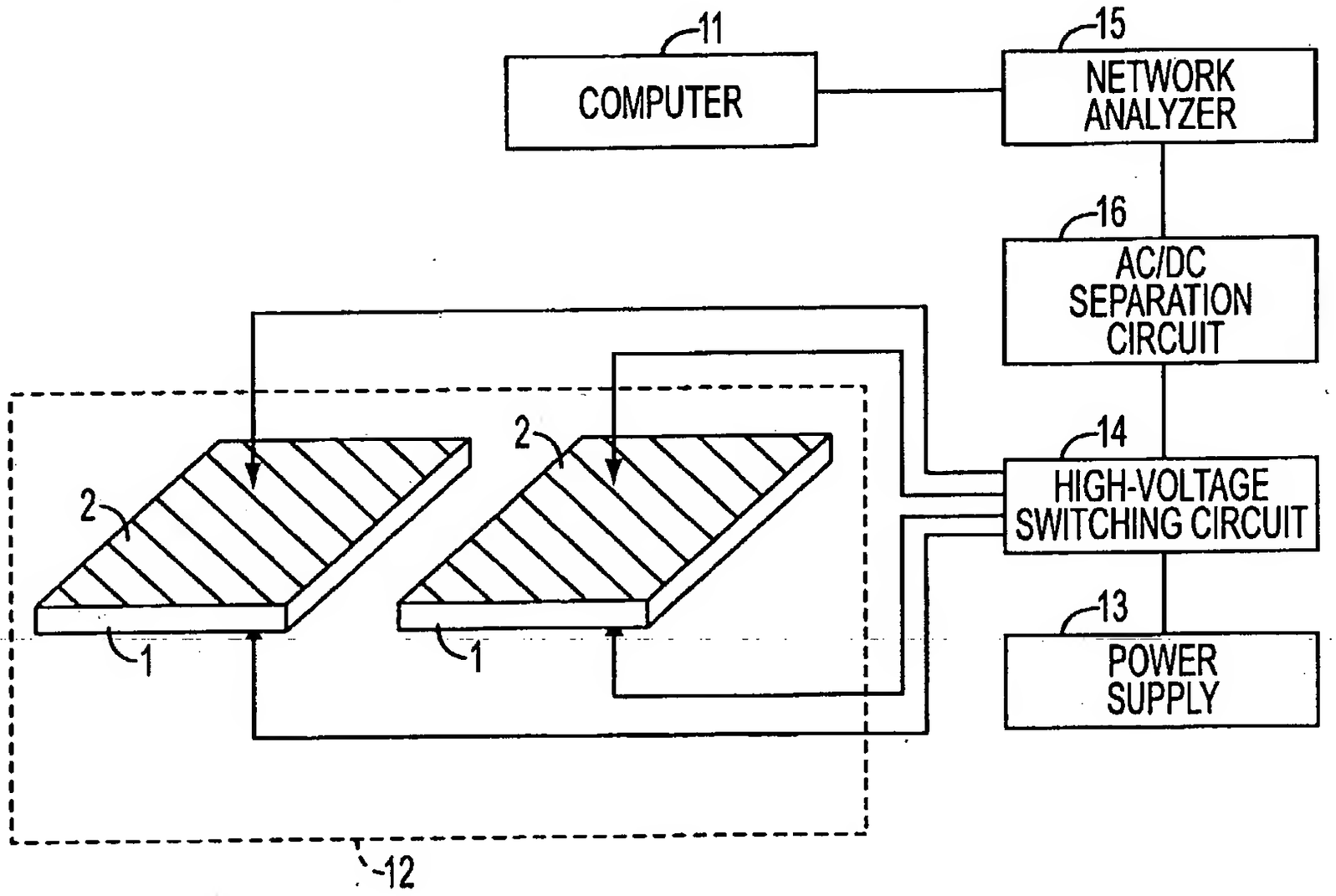

FIG. 1

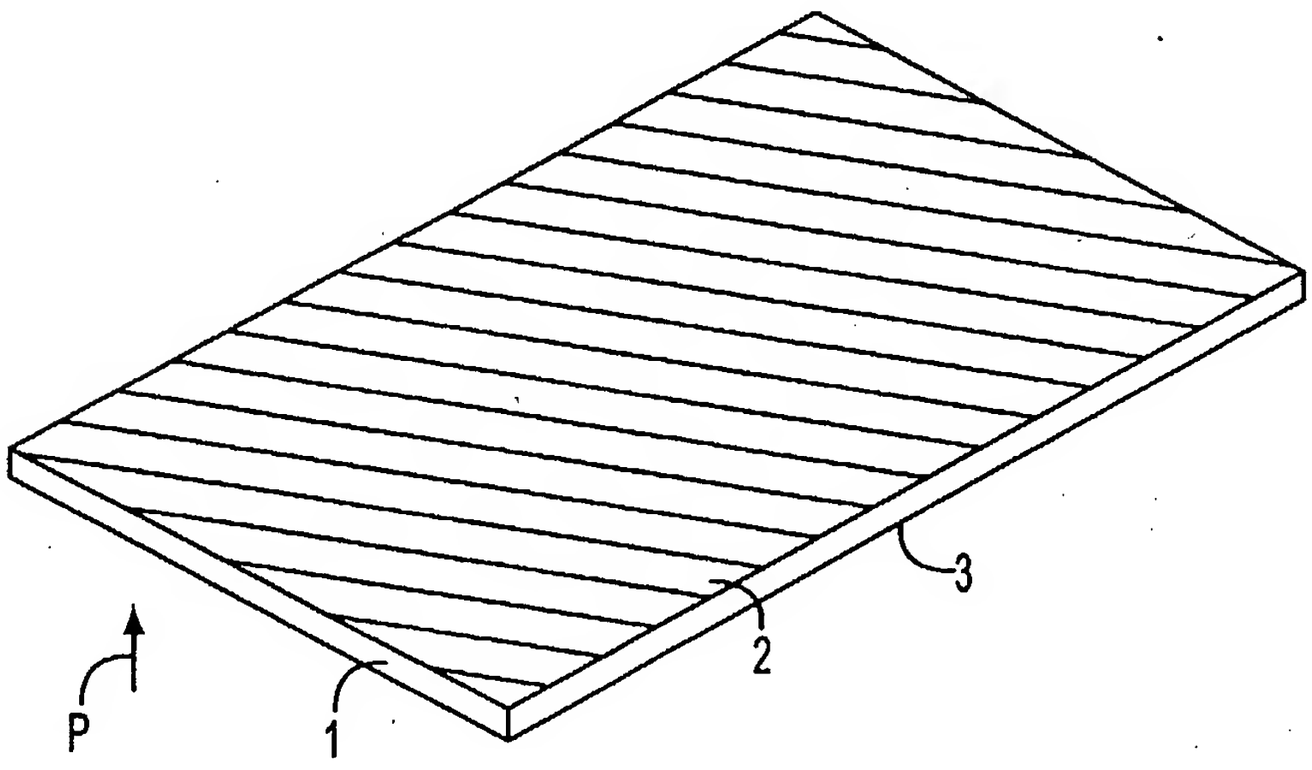

FIG. 2

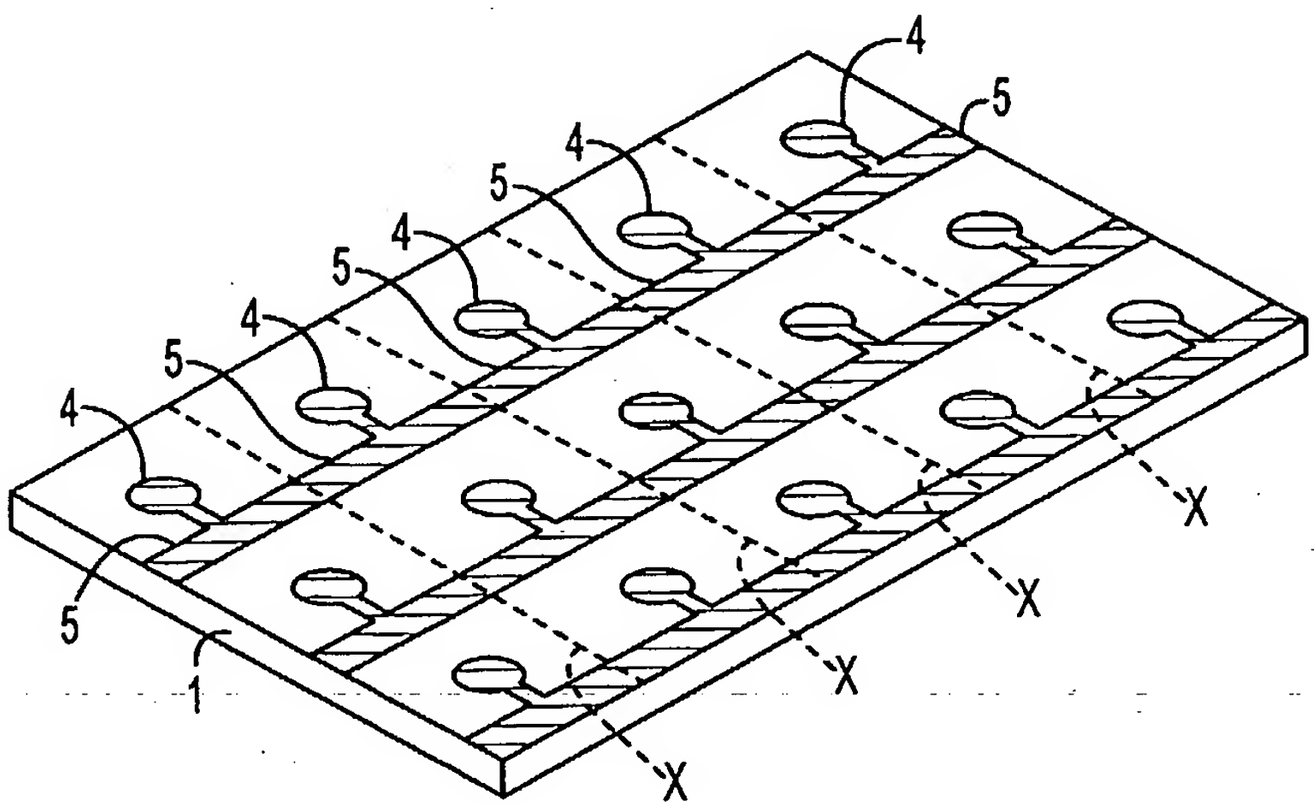

FIG. 3

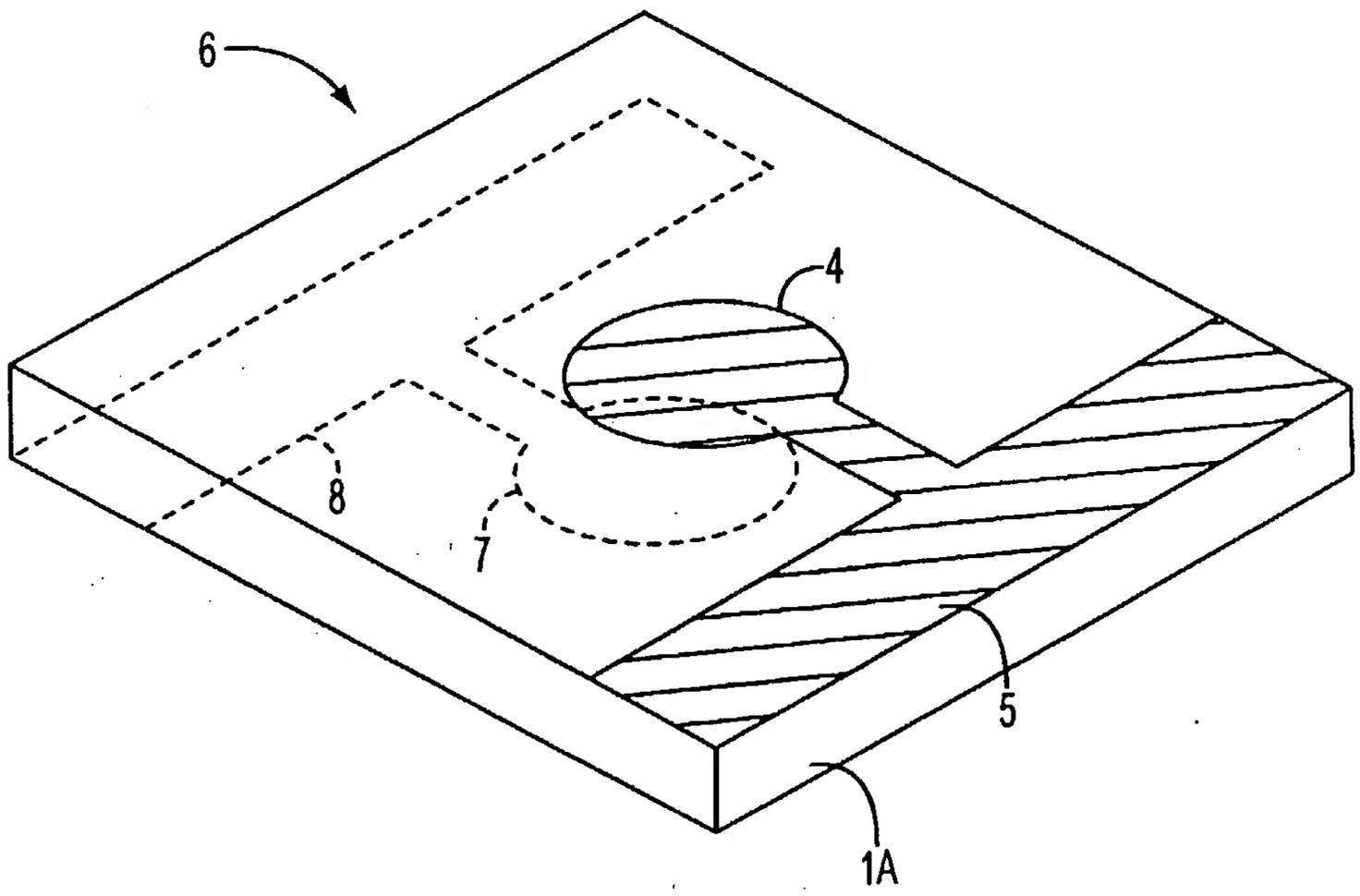

FIG. 4

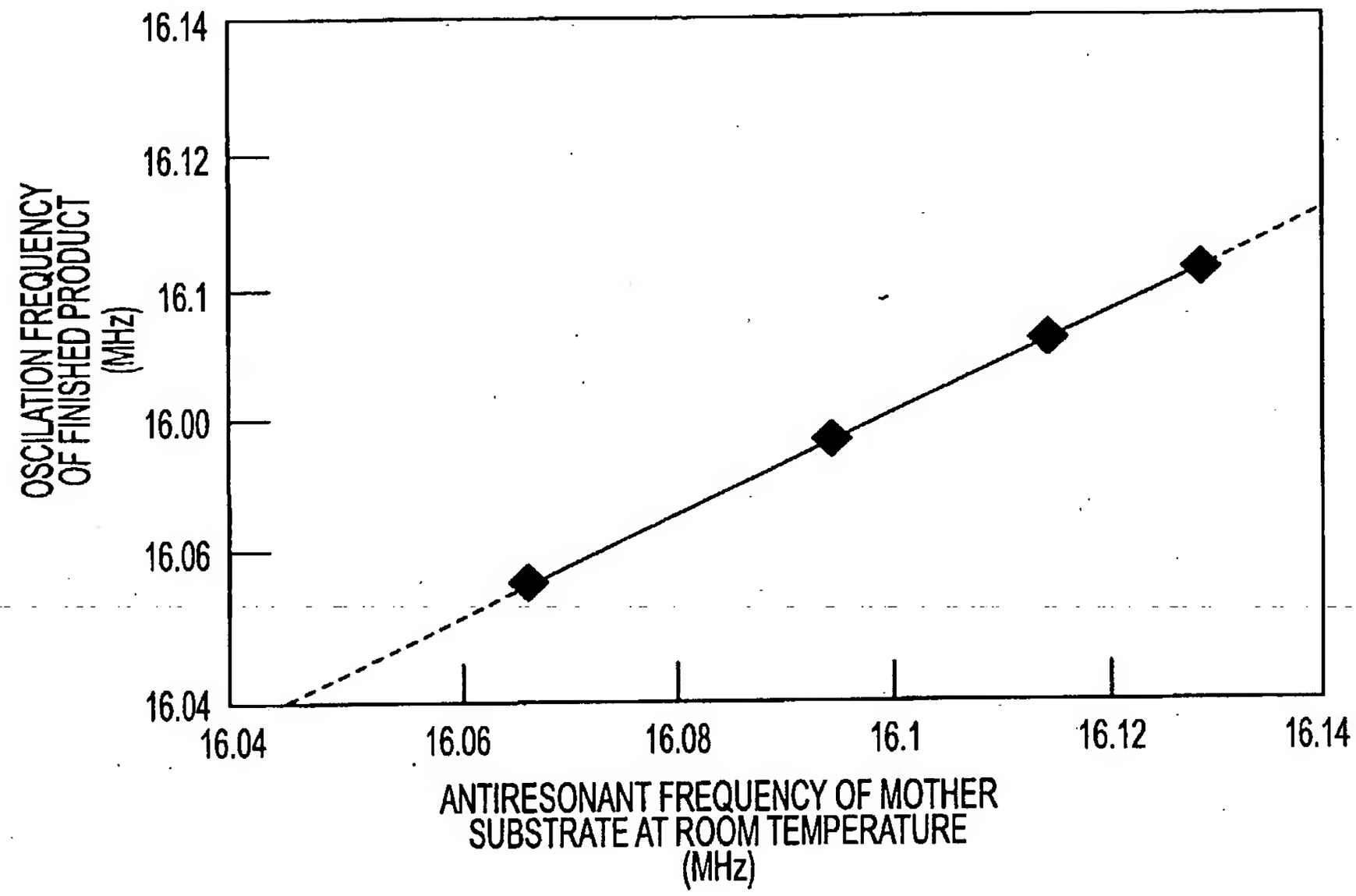

FIG. 5

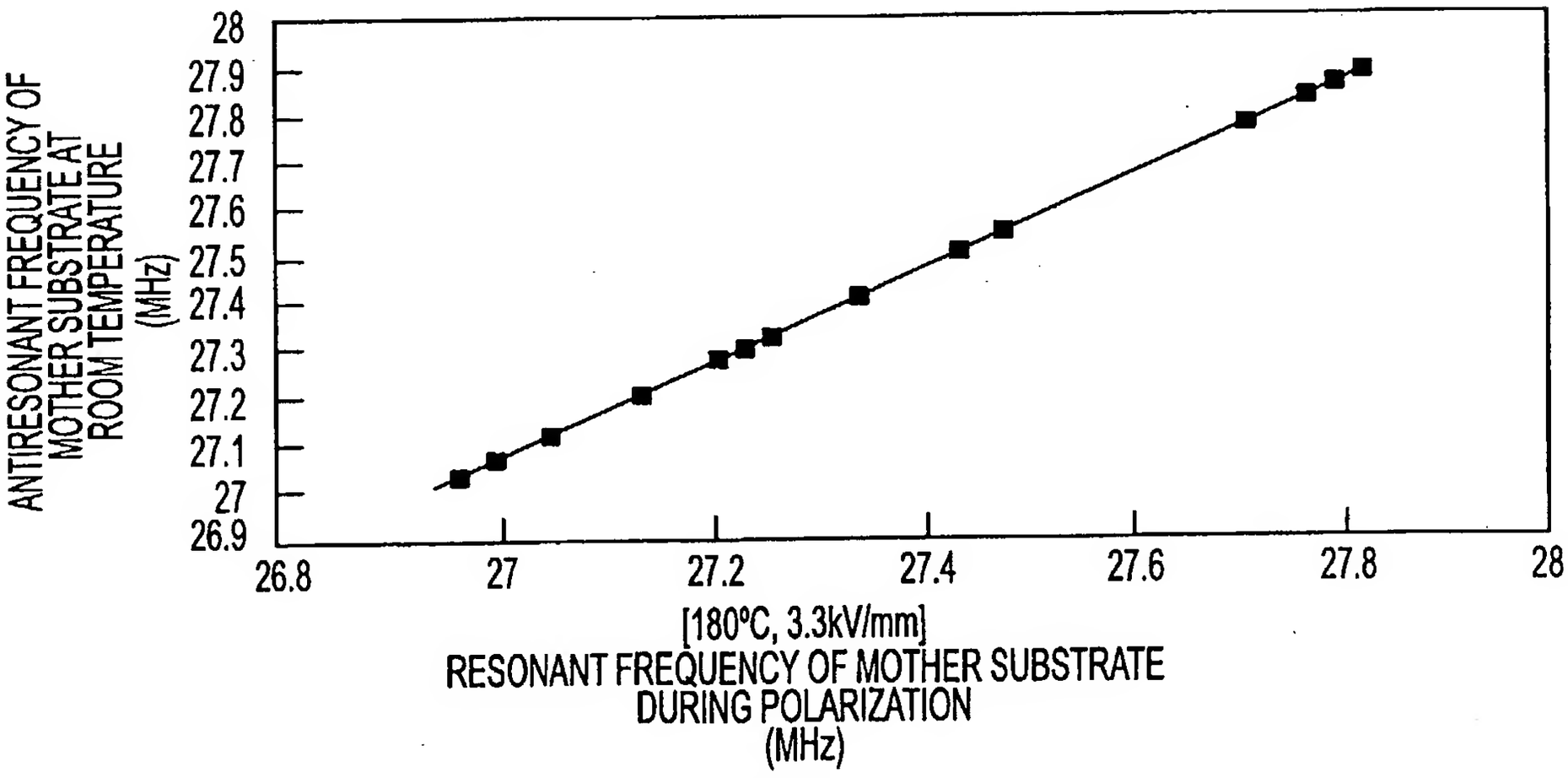

FIG. 6

APPLN. FILING DATE: DECEMBER 20, 2001
TITLE: MANUFACTURING METHOD FOR CERAMIC OSCILLATOR
INVENTOR: NAOKI FUJII ET AL.
APPLICATION SERIAL NO: 10/022,278

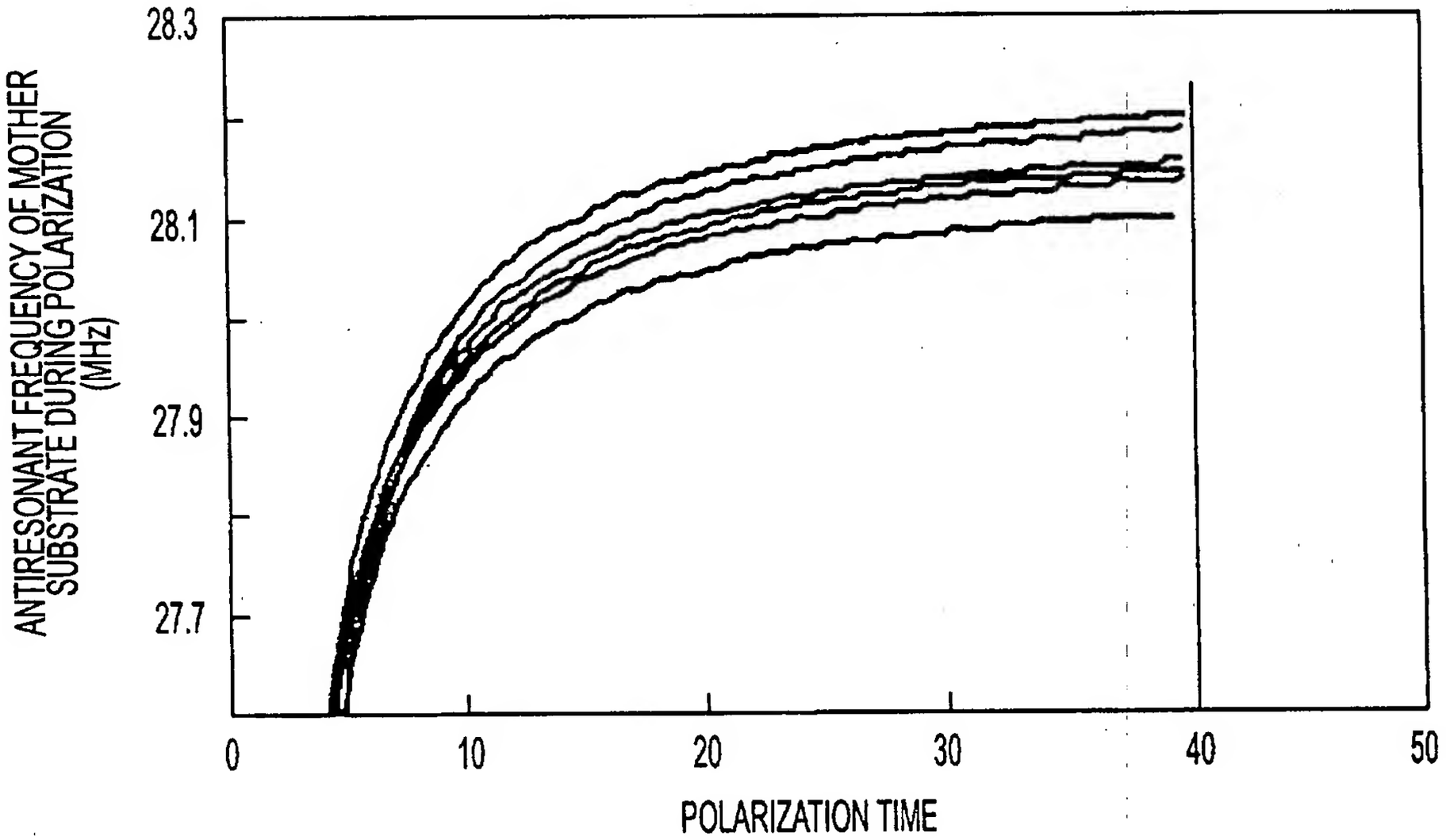

FIG. 7

APPLN. FILING DATE: DECEMBER 20, 2001
TITLE: MANUFACTURING METHOD FOR CERAMIC OSCILLA
INVENTO: NAOKI FUJII ET AL.
APPLICATION SERIAL NO: 10/022,278
SHEET 5 of 5

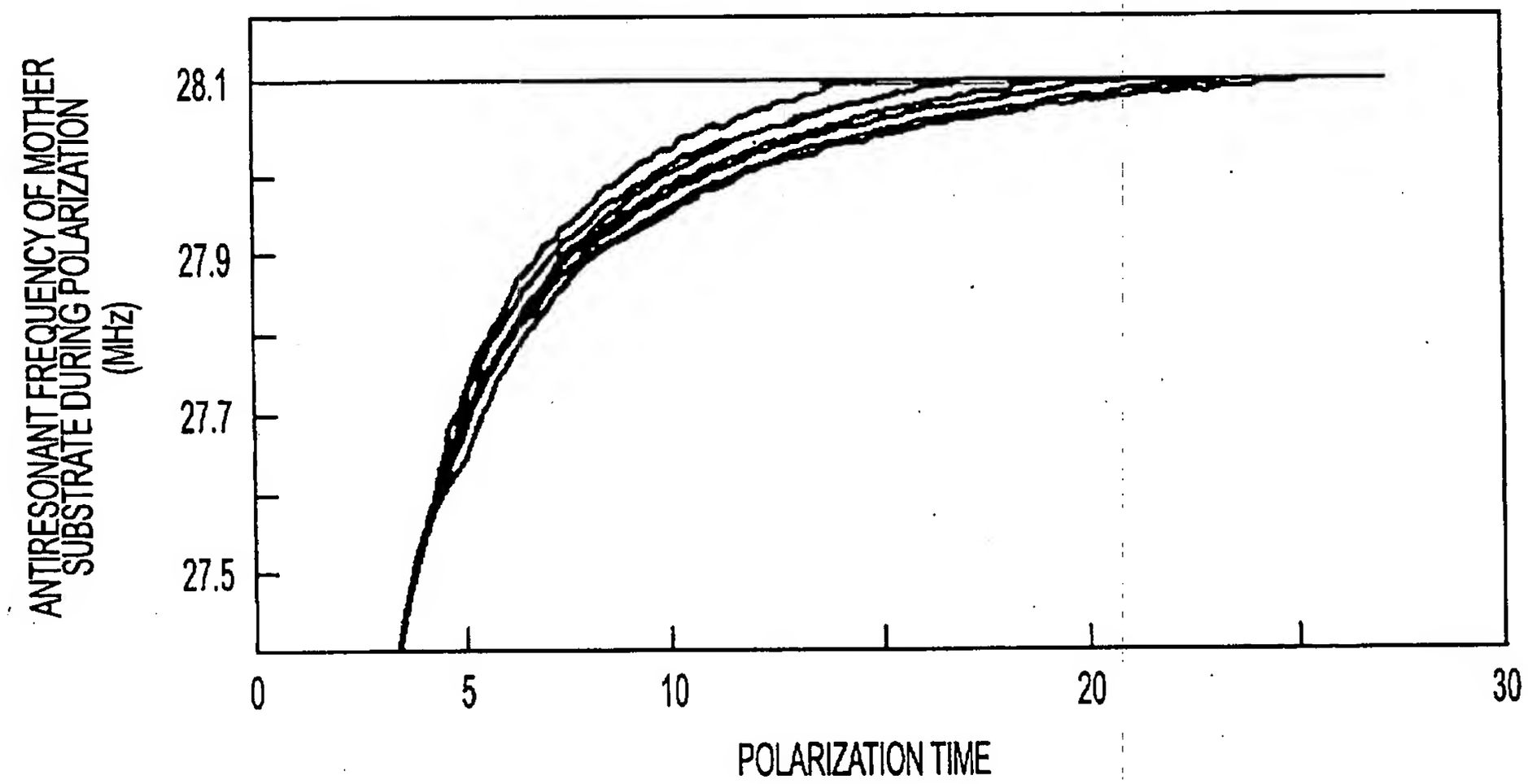

FIG. 8